

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1508171	recess\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 10:31
L2	63762	CMP or "CMP" or (chemical adj mechanical adj polish\$4) or chemical-mechanical-polish\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 10:31
L3	35077	etchback or etchedback or etch-back or etched-back or backetching or back-etching or backetching or back-etch\$3 or (etch\$3 near2 back)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 10:31
L4	709065	capacitor or capacitors	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 10:31
L5	490358	(bottom or lower) near2 (electrode or electrodes or plate or plates)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 10:31
L6	3726	((438/3) or (438/239) or (438/240) or (438/250) or (438/393)).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/09/29 10:32
L7	15590	contact adj plug\$1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 10:33
L8	15675	capacitor\$1 adj element\$1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 10:33
L9	54976	recess\$4 near10 (isolat\$4 or dielectric\$1 or insulat\$5 or oxide\$1)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 10:34

L10	59774	planariz\$8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 10:35
L11	10	7 and 8 and 9 and 10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 10:37
L12	799	1 and 2 and 3 and 4 and 5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 10:37
L13	169	12 and 6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 10:38